



US00D946207S

(12) **United States Design Patent**  
**Nakamura et al.**

(10) **Patent No.:** **US D946,207 S**  
(45) **Date of Patent:** **\*\* Mar. 15, 2022**

(54) **COSMETIC MASK**

(71) Applicant: **TAIKI CORP., LTD.**, Osaka (JP)

(72) Inventors: **Koji Nakamura**, Osaka (JP); **Yasuko Nakamura**, Osaka (JP)

(73) Assignee: **TAIKI CORP., LTD.**, Osaka (JP)

(\*\*) Term: **15 Years**

(21) Appl. No.: **29/764,373**

(22) Filed: **Dec. 30, 2020**

(30) **Foreign Application Priority Data**

Dec. 2, 2020 (JP) ..... 2020-025947 D

(51) **LOC (13) Cl.** ..... **28-03**

(52) **U.S. Cl.**  
USPC ..... **D28/7**

(58) **Field of Classification Search**  
USPC ..... D28/7, 8, 99; D29/108; D21/660  
CPC ..... A45D 44/002; A45D 2200/1009  
See application file for complete search history.

(56) **References Cited**

**U.S. PATENT DOCUMENTS**

D646,842 S \* 10/2011 Roman ..... D28/7  
D726,368 S \* 4/2015 Durocher ..... D28/7

D734,896 S \* 7/2015 Mam ..... D29/108  
D763,515 S \* 8/2016 Chang ..... D29/108  
D836,835 S \* 12/2018 Hazem ..... D28/7  
D849,999 S \* 5/2019 Bae ..... D28/7  
D861,244 S \* 9/2019 Chang ..... D28/7  
D864,479 S \* 10/2019 Hasegawa ..... D28/4  
D884,964 S \* 5/2020 Wang ..... D28/7  
D886,369 S \* 6/2020 Hasegawa ..... D28/4  
D892,401 S \* 8/2020 Hongo ..... D28/7

\* cited by examiner

*Primary Examiner* — Zenia I Bennett

(74) *Attorney, Agent, or Firm* — JCIPRNET

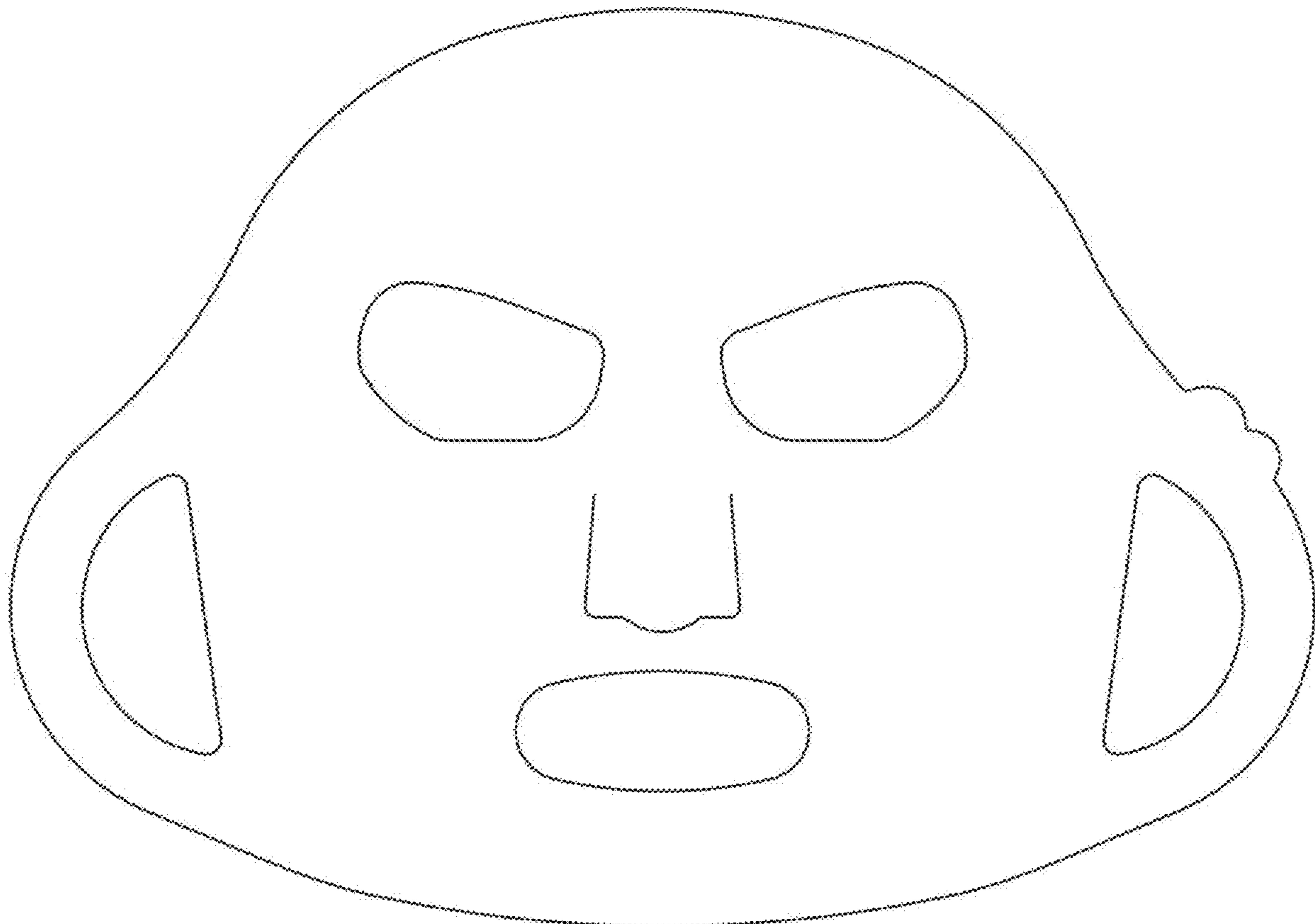
(57) **CLAIM**

The ornamental design for a cosmetic mask, as shown and described.

**DESCRIPTION**

FIG. 1 is a perspective view of a cosmetic mask showing our new design;  
FIG. 2 is a front view thereof, the rear view being a mirror image thereof;  
FIG. 3 is a left side view thereof;  
FIG. 4 is a right side view thereof;  
FIG. 5 is a top view thereof; and,  
FIG. 6 is a bottom view thereof.

**1 Claim, 3 Drawing Sheets**



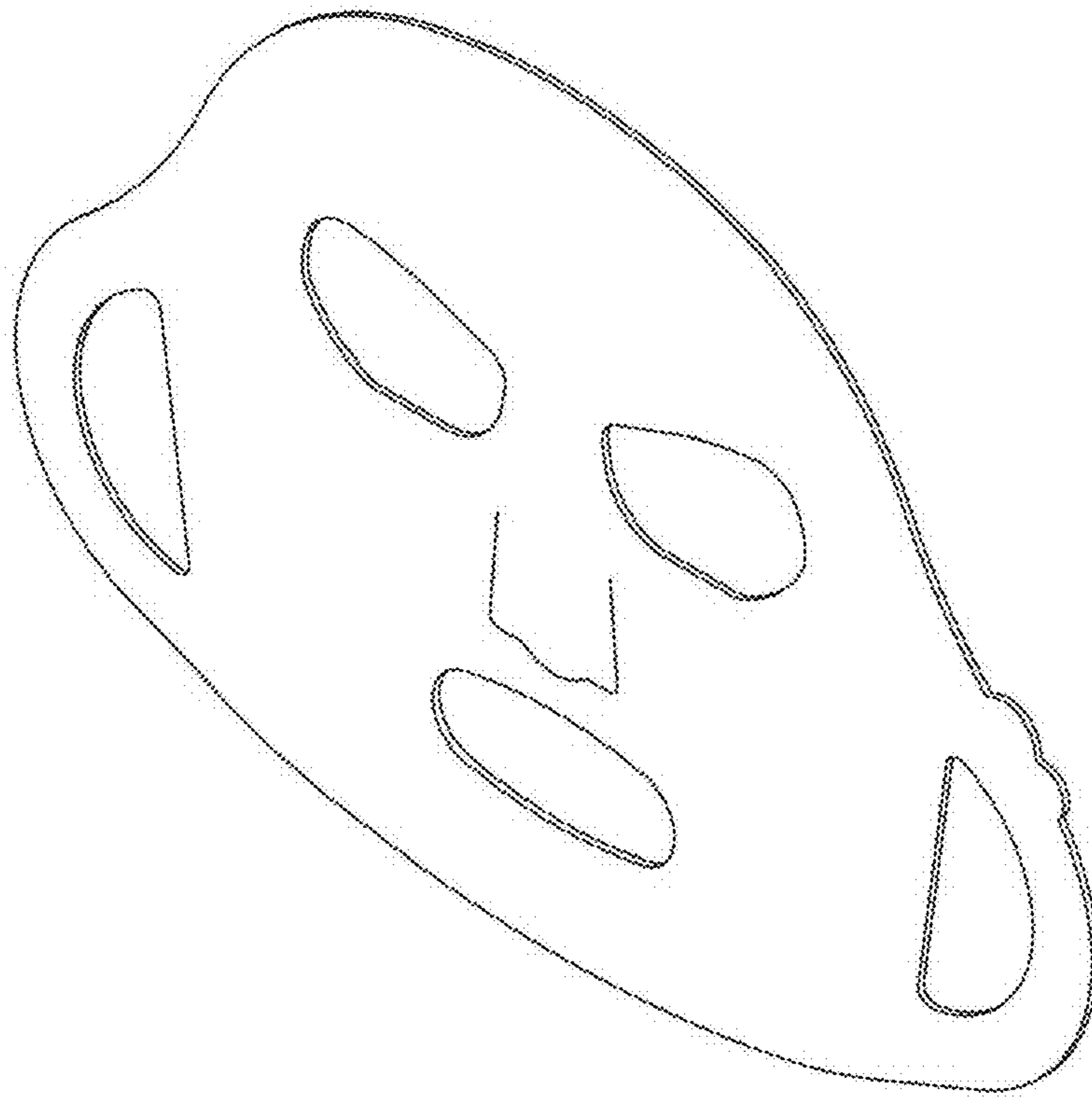


FIG. 1

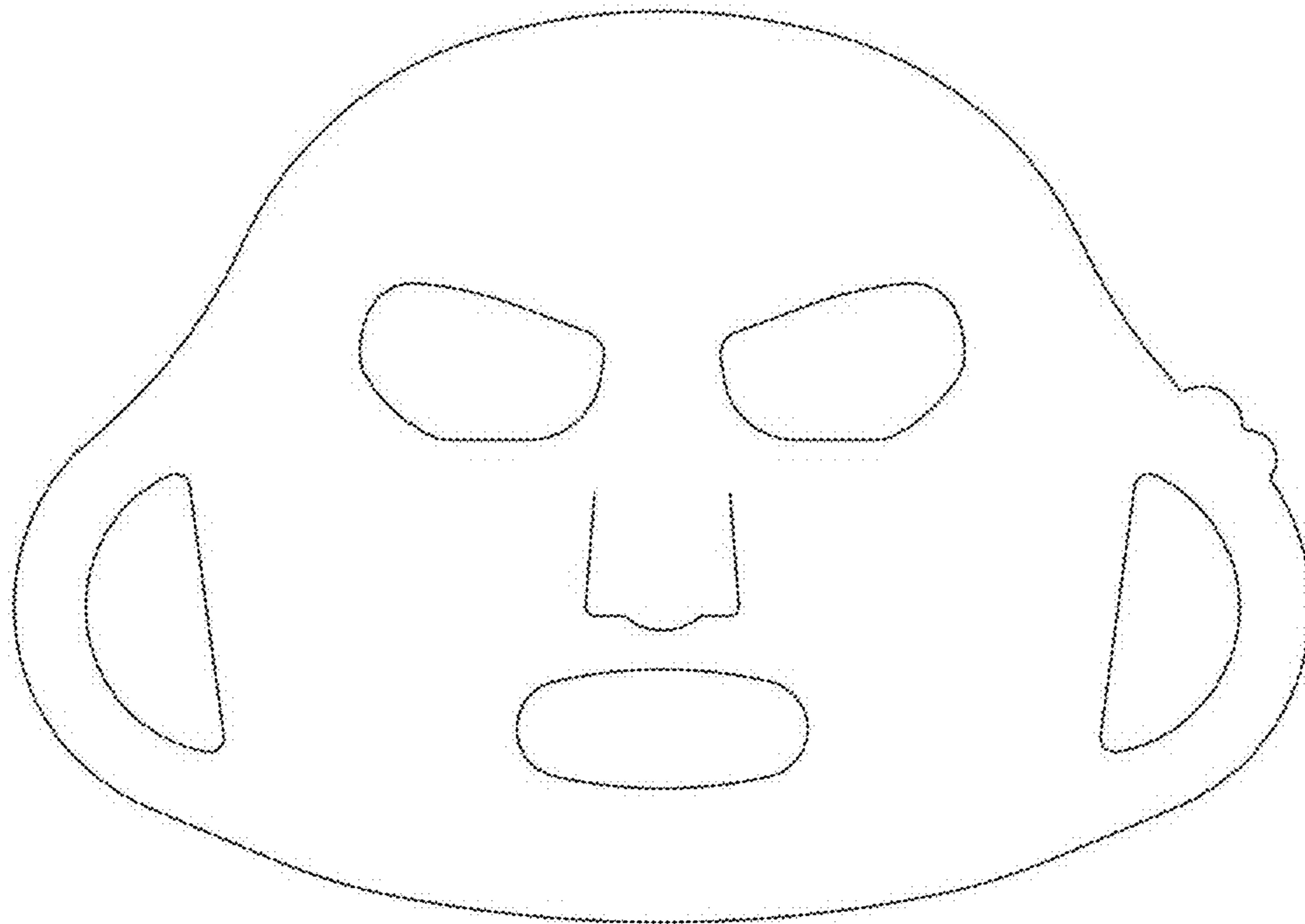


FIG. 2



FIG. 3

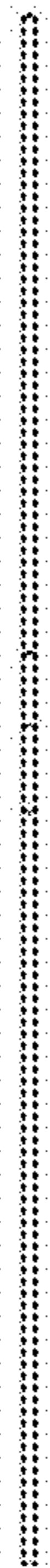
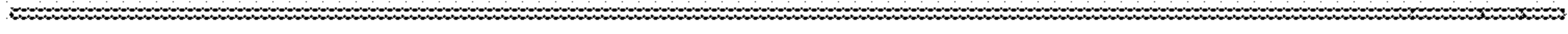
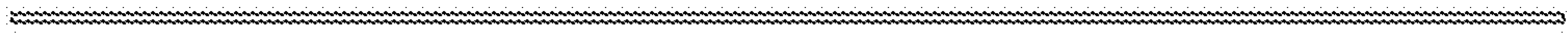


FIG. 4



**FIG. 5**



**FIG. 6**